

Supplementary information for

**Molecular and dissociative adsorption of water and hydrogen sulfide at
perfect and defective Cu(110) surfaces**

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- Adsorption site names:

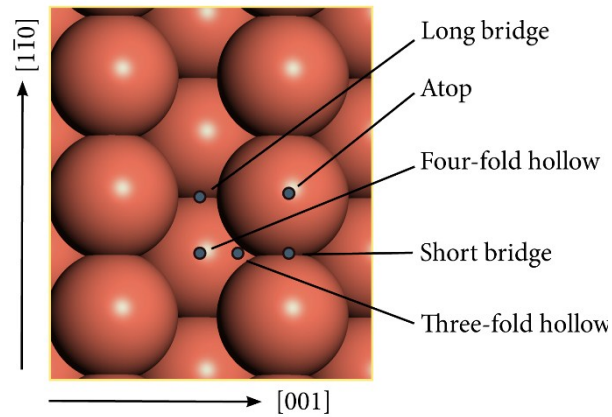


Figure S1. Adsorption site names for the Cu(110) surface employed in this work.

- Measurements for understanding the relaxation and reconstruction upon adsorption of HS and HO on the perfect and on the defective Cu(110):

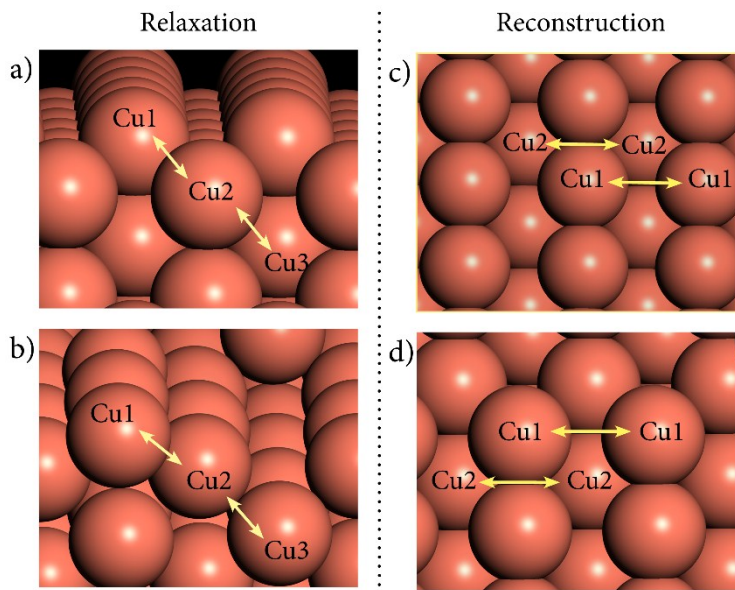


Figure S2. Relaxation and reconstruction for the perfect (a), (c) and defective (b), (d) Cu(110). The distances between the atoms shown on Table 2 were measured as indicated by the arrows.